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Alkaline Texturization of Monocrystalline Solar Wafers

Increase cell efficiency and lower production costs by optimizing the alkaline texturing of monocrystalline silicon wafers. Our chemical additives (ALKA-TEX) based on organic molecules are the first to offer IPA-free processes with excellent stability and homogeneity. The reduced cost of wastewater treatment presents a great opportunity to lower production costs permanently. Our additives are also suitable for both standard lines and leading-edge cell technologies. Together with our experienced engineers we offer ALKA-TEX services (e.g. on-site support, development) for each application to find a perfect match of chemical recipe and the individual demand of alkaline texturing.

Chemical additive for optimizing texturing in monocrystalline silicon wafers

Our chemical additive is capable of increasing the efficiency of a standard cell in mass production to more than 20%.

> [ALKA-TEX.Free](#)

Chemical additive with extended shelf life

An enhancement of the ALKA-TEX .Free additive, ALKA-TEX .Free+ has the same properties, but increases shelf life to up to 6 months.

[> ALKA-TEX.Free+](#)

Texturing optimization additive optimized for inline machines

The newly developed, highly active molecule allows users to significantly reduce process times.

[> ALKA-TEX 8](#)

Chemical additive for improving the appearance of monocrystalline solar wafers

Shorter process times and improved appearance: The molecule of this additive offers greater adhesion to the silicon surface.

[> ALKA-TEX 9](#)

Chemical additive for optimizing wafer texture

This additive, an enhancement of ALKA-TEX .9, reduces consumption of chemical materials.

[> ALKA-TEX 9+](#)

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Contact us!

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